

CLAIMS

1. A polishing solution for metal comprising
(1) an additive which permits chemical mechanical
polishing to be carried out without solid abrasive grains,
(2) an oxidizing agent, and (3) water.

2. A polishing solution for metal comprising
(1) an oxidizing agent, (2) an oxidized-metal dissolving
agent, (3) a metal etching rate inhibitor, and (4) water.